Ref #	Hits	Search Query	DBs	Default Operat or	Plura Is	Time Stamp
S69	33	(hydrogen H2 "H.sub.2") with (nitrogen N2 "N.sub. 2") with (fluorine F2 "F. sub.2") same (plasma etch\$3) and etch\$3 with (silane siloxane vinyltrimethoxysilane siloxane-containing TEOS HMDSO)	US-PGPU B; USPAT	OR	ON	2005/09/17 18:56
S70	2	(hydrogen H2 "H.sub.2") with (nitrogen N2 "N.sub. 2") with (fluorine F2 "F. sub.2") same (plasma etch\$3) same bcb	US-PGPU B; USPAT	OR	ON	2005/09/17 18:03
S71	1	("2002/0155639").URPN.	USPAT	OR	OFF	2005/09/17 18:08
S72	25	("20020052125" "20020155639" "4330384" "4333793" "4529860" "4636281" "4707218" "4838991" "5017403" "5116460" "5294296" "5459099" "5750441" "5882535" "5932491" "6140171" "6168726" "6207583" "6294314" "6326302" "6331380" "6350675" "6358838" "6388226" "6426300").PN. OR ("6699792").URPN.	US-PGPU B; USPAT; USOCR	OR	OFF	2005/09/17 18:08
S73	25	S72 and ((hydrogen H2 "H.sub.2") (nitrogen N2 "N.sub.2") (fluorine F2 "F. sub.2") etch\$3 silane siloxane vinyltrimethoxysilane siloxane-containing TEOS HMDSO bcb)	US-PGPU B; USPAT	OR	ON	2005/09/17 19:50

						
S74	793	(((nitrogen N2 "N.sub.2") with ((hydrogen H2 "H. sub.2") and (fluorine F2 "F.sub.2")))((hydrogen H2 "H.sub.2") with ((nitrogen N2 "N.sub.2") and (fluorine F2 "F.sub. 2")))((fluorine F2 "F.sub. 2") with ((nitrogen N2 "N. sub.2") and (hydrogen H2 "H.sub.2"))) ((hydrogen H2 "H.sub.2") with (NF3 "NF.sub.3" nitrogentrifluori?e nitrogen adj \$3fluoride)) ((nitrogen N2 "N.sub.2") with (hydrogen adj fluori?e HF hydrofluoric)) ((nitrogen N2 "N.sub.2") with (fluorohydrocarbon hydrofluorocarbon CFH CHF fluorocarbon CH2F2 CF2H2 CHF3 CF3H CH3F	US-PGPU B; USPAT	OR	ON	2005/09/17 19:24
		CFH3 "CH.sub.2 F.sub.2" "CF.sub.2 H.sub.2" "CHF. sub.3" "CF.sub.3 H" "CH. sub.3 F" "CFH.sub.3"))) same (plasma etch\$3) and etch\$3 with (silane siloxane vinyltrimethoxysilane siloxane-containing (Si silicon) adj containing adj (organic polymer) TEOS HMDSO hybrid composite \$2organic/\$2organic \$2organic-\$2organic organic near2 inorganic (interlayer interlevel intermetal) near dielectric ILD)				

						<u>_</u>
S76	517	((nitrogen N2 "N.sub.2") with (hydrogen H2 "H. sub.2" fluorine F2 "F.sub. 2") (hydrogen H2 "H.sub. 2") with (fluorine F2 "F. sub.2") (fluorine F2 "F. sub.2") with (forming adj gas N2/F2 F2/N2) (hydrogen H2 "H.sub.2") with (NF3 "NF.sub.3" nitrogentrifluori?e nitrogen adj \$3fluoride) (nitrogen N2 "N.sub.2") with (hydrogen adj fluori?e HF hydrofluoric) (nitrogen N2 "N.sub.2") with (fluorohydrocarbon hydrofluorocarbon CFH CHF fluorocarbon CH2F2 CF2H2 CHF3 CF3H CH3F CFH3 "CH.sub.2 F.sub.2" "CF.sub.2 H.sub.2" "CHF. sub.3" "CF.sub.3 H" "CH. sub.3 F" "CFH.sub.3")) with (plasma etch\$3) with (silane siloxane vinyltrimethoxysilane siloxane-containing (Si silicon) adj containing adj (organic polymer) TEOS HMDSO hybrid composite \$2organic-\$2organic \$2organic near2 inorganic (interlayer interlevel intermetal) near dielectric	US-PGPU B; USPAT	OR	ON	2005/09/17 19:34
		ILD BCB)				

Cin	10	((-1 NO HAL OH)	HC DCDI	00	ON	2005/00/17
S77	49	((nitrogen N2 "N.sub.2")	US-PGPU	OR	ON	2005/09/17
		with (hydrogen H2 "H.	B;			19:34
		sub.2" fluorine F2 "F.sub.	USPAT			
		2") (hydrogen H2 "H.sub.				
		2") with (fluorine F2 "F.				
		sub.2") (fluorine F2 "F.				
		sub.2") with (forming adj				
		gas N2/F2 F2/N2)				
		(hydrogen H2 "H.sub.2")				
		with (NF3 "NF.sub.3"				
		nitrogentrifluori?e				
		nitrogen adj \$3fluoride)				
		(nitrogen N2 "N.sub.2")				
		with (hydrogen adj				
		fluori?e HF hydrofluoric)				
		(nitrogen N2 "N.sub.2")				
i		with (fluorohydrocarbon	į			
		hydrofluorocarbon CFH				
		CHF fluorocarbon CH2F2				·
		CF2H2 CHF3 CF3H CH3F				·
		CFH3 "CH.sub.2 F.sub.2"				
		"CF.sub.2 H.sub.2" "CHF.				
		sub.3" "CF.sub.3 H" "CH.				
		sub.3 F" "CFH.sub.3"))				
		near2 (plasma etch\$3)				
		, , ,				
		with (silane siloxane				
		vinyltrimethoxysilane				
		siloxane-containing (Si				
		silicon) adj containing adj		,		
		(organic polymer) TEOS				
		HMDSO hybrid composite				
		\$2organic/\$2organic				
		\$2organic-\$2organic				
		organic near2 inorganic				
		(interlayer interlevel				
		intermetal) near dielectric				
•		ILD BCB)				

S78	69	((nitrogen N2 "N.sub.2")	US-PGPU	OR	ON	2005/09/17
3/6	09	with (hydrogen H2 "H.	B;		014	19:35
		sub.2" fluorine F2 "F.sub.	USPAT			19.55
		1	USPAT			
		2") (hydrogen H2 "H.sub.				
		2") with (fluorine F2 "F.		:	:	
		sub.2") (fluorine F2 "F.				
		sub.2") with (forming adj				
	:	gas N2/F2 F2/N2)				
		(hydrogen H2 "H.sub.2")		,		
ļ		with (NF3 "NF.sub.3"				
		nitrogentrifluori?e				
		nitrogen adj \$3fluoride)				
<u> </u>		(nitrogen N2 "N.sub.2")				
		with (hydrogen adj				
		fluori?e HF hydrofluoric)				
	1	(nitrogen N2 "N.sub.2")				
		with (fluorohydrocarbon				
		hydrofluorocarbon CFH				
		CHF fluorocarbon CH2F2				
		CF2H2 CHF3 CF3H CH3F				
		CFH3 "CH.sub.2 F.sub.2"				
		"CF.sub.2 H.sub.2" "CHF.				
		sub.3" "CF.sub.3 H" "CH.				
		sub.3 F" "CFH.sub.3"))				·
		with (plasma etch\$3)		,		
		near2 (silane siloxane				
		vinyltrimethoxysilane				•
		siloxane-containing (Si				
		silicon) adj containing adj				
		(organic polymer) TEOS				
		HMDSO hybrid composite			·	
		\$2organic/\$2organic				
		\$2organic-\$2organic				
		organic near2 inorganic	İ			
		(interlayer interlevel				
		intermetal) near dielectric				
		ILD BCB)				
		150 000)				

S79	28	((nitrogen N2 "N.sub.2") with (hydrogen H2 "H. sub.2" fluorine F2 "F.sub. 2") (hydrogen H2 "H.sub. 2") with (fluorine F2 "F. sub.2") (fluorine F2 "F. sub.2") with (forming adj gas N2/F2 F2/N2) (hydrogen H2 "H.sub.2") with (NF3 "NF.sub.3" nitrogentrifluori?e nitrogen adj \$3fluoride) (nitrogen N2 "N.sub.2") with (hydrogen adj fluori?e HF hydrofluoric) (nitrogen N2 "N.sub.2") with (fluorohydrocarbon hydrofluorocarbon CFH CHF fluorocarbon CH2F2 CF2H2 CHF3 CF3H CH3F CFH3 "CH.sub.2 F.sub.2" "CF.sub.2 H.sub.2" "CHF. sub.3" "CF.sub.3 H" "CH. sub.3 F" "CFH.sub.3")) with (plasma etch\$3) near (silane siloxane vinyltrimethoxysilane siloxane-containing (Si silicon) adj containing adj (organic polymer) TEOS HMDSO hybrid composite \$2organic/\$2organic \$2organic near2 inorganic (interlayer interlevel intermetal) near dielectric ILD BCB)	US-PGPU B; USPAT	OR	ON	2005/09/17 19:37
S80	45	S77 not S79	US-PGPU B; USPAT	OR	ON	2005/09/17 19:58
S81	39	S78 not (S77 S79)	US-PGPU B; USPAT	OR	ON	2005/09/17 19:59

S82	4	("6331481" "6372636" "6429122").PN. OR ("6787446").URPN.	US-PGPU B; USPAT; USOCR	OR	OFF	2005/09/17 20:04
S83	12	("5459105" "5780163" "5814563" "5817572" "6059553" "6124154" "6187666" "6221755" "6228751" "6323142" "6451504").PN. OR ("6632746").URPN.	B; USPAT;	OR	OFF	2005/09/17 20:06

						2005/06/45
S84	179	((nitrogen N2 "N.sub.2")	EPO;	OR	ON	2005/09/17
		with (hydrogen H2 "H.	JPO;			20:24
		sub.2" fluorine F2 "F.sub.	DERWEN			
		2") (hydrogen H2 "H.sub.	T;			
		2") with (fluorine F2 "F.	IBM_TDB			
		sub.2") (fluorine F2 "F.				
		sub.2") with (forming adj				
		gas N2/F2 F2/N2)	5			
		(hydrogen H2 "H.sub.2")				
		with (NF3 "NF.sub.3"				
		nitrogentrifluori?e				
		nitrogen adj \$3fluoride)				
		(nitrogen N2 "N.sub.2")				
		with (hydrogen adj				
		fluori?e HF hydrofluoric)				
		(nitrogen N2 "N.sub.2")				·
1		with (fluorohydrocarbon				
		hydrofluorocarbon CFH				
		CHF fluorocarbon CH2F2				
		CF2H2 CHF3 CF3H CH3F				
		CFH3 "CH.sub.2 F.sub.2"				
		"CF.sub.2 H.sub.2" "CHF.				
		sub.3" "CF.sub.3 H" "CH.				
' '		sub.3 F" "CFH.sub.3"))				
		same (plasma etch\$3)				
1.		same (silane siloxane				
		vinyltrimethoxysilane				
		siloxane-containing (Si	-			
		silicon) adj containing adj				
		(organic polymer) TEOS				
		HMDSO hybrid composite				
		\$2organic/\$2organic				
		\$2organic-\$2organic				
		organic near2 inorganic				
		(interlayer interlevel				
		intermetal) near dielectric				
		ILD BCB)				
		ILD DCD)				

S87	5	((nitrogen N2 "N.sub.2")	EPO;	OR	ON	2005/09/17
		with (hydrogen H2 "H.	JPO;			20:18
		sub.2" fluorine F2 "F.sub.	DERWEN	l i		
		2") (hydrogen H2 "H.sub.	Т;			
		2") with (fluorine F2 "F.	IBM_TDB			
		sub.2") (fluorine F2 "F.	_			
		sub.2") with (forming adj			:	
		gas N2/F2 F2/N2)				
		(hydrogen H2 "H.sub.2")				
		with (NF3 "NF.sub.3"				
		nitrogentrifluori?e				
		nitrogen adj \$3fluoride)				
		(nitrogen N2 "N.sub.2")				
		with (hydrogen adj				
		fluori?e HF hydrofluoric)				
		(nitrogen N2 "N.sub.2")				
		with (fluorohydrocarbon				
		hydrofluorocarbon CFH			,	
		CHF fluorocarbon CH2F2				
		CF2H2 CHF3 CF3H CH3F				
		CFH3 "CH.sub.2 F.sub.2"	_			
		"CF.sub.2 H.sub.2" "CHF.				
		sub.3" "CF.sub.3 H" "CH.				
		sub.3 F" "CFH.sub.3"))				
'		with (plasma etch\$3) near	·	,		
		(silane siloxane				
		vinyltrimethoxysilane				
		siloxane-containing (Si				
		silicon) adj containing adj				,
		(organic polymer) TEOS				
		HMDSO hybrid composite				
		\$2organic/\$2organic				
		\$2organic-\$2organic				
		organic near2 inorganic				
		(interlayer interlevel				
	,	intermetal) near dielectric				
		ILD BCB)				

S88	10	((nitrogen N2 "N.sub.2")	EPO;	OR	ON	2005/09/17
		with (hydrogen H2 "H.	JPO;			20:21
		sub.2" fluorine F2 "F.sub.	DERWEN			
		2") (hydrogen H2 "H.sub.	T;			
		2") with (fluorine F2 "F.	IBM_TDB			
		sub.2") (fluorine F2 "F.	15/1_155			
		sub.2") with (forming adj				
		gas N2/F2 F2/N2)				
		(hydrogen H2 "H.sub.2")				
		with (NF3 "NF.sub.3"				
		nitrogentrifluori?e		•		
ŀ		nitrogen adj \$3fluoride)				
		(nitrogen N2 "N.sub.2")				
		, ,	,			
		with (hydrogen adj		·		
		fluori?e HF hydrofluoric)				
		(nitrogen N2 "N.sub.2")				
		with (fluorohydrocarbon				
		hydrofluorocarbon CFH			•	
		CHF fluorocarbon CH2F2				
		CF2H2 CHF3 CF3H CH3F				
ļ		CFH3 "CH.sub.2 F.sub.2"			ĺ	
		"CF.sub.2 H.sub.2" "CHF.				
		sub.3" "CF.sub.3 H" "CH.				
		sub.3 F" "CFH.sub.3"))	<u> </u> -			
		with (plasma etch\$3)				
		near2 (silane siloxane		,		
		vinyltrimethoxysilane				
		siloxane-containing (Si				'
	i	silicon) adj containing adj				
		(organic polymer) TEOS				
		HMDSO hybrid composite	:			
		\$2organic/\$2organic				
		\$2organic-\$2organic				
		organic near2 inorganic				
		(interlayer interlevel				
		intermetal) near dielectric				
		ILD BCB)		•		

	· · · · · · · · · · · · · · · · · · ·					
S89	13	((nitrogen N2 "N.sub.2") with (hydrogen H2 "H. sub.2" fluorine F2 "F.sub. 2") (hydrogen H2 "H.sub. 2") with (fluorine F2 "F. sub.2") (fluorine F2 "F. sub.2") with (forming adj gas N2/F2 F2/N2) (hydrogen H2 "H.sub.2") with (NF3 "NF.sub.3" nitrogentrifluori?e nitrogen adj \$3fluoride) (nitrogen N2 "N.sub.2") with (hydrogen adj fluori?e HF hydrofluoric) (nitrogen N2 "N.sub.2") with (fluorohydrocarbon hydrofluorocarbon CFH CHF fluorocarbon CH2F2 CF2H2 CHF3 CF3H CH3F CFH3 "CH.sub.2 F.sub.2" "CF.sub.2 H.sub.2 "CHF. sub.3" "CF.sub.3 H" "CH. sub.3 F" "CFH.sub.3")) near2 (plasma etch\$3) with (silane siloxane vinyltrimethoxysilane siloxane-containing (Si silicon) adj containing adj (organic polymer) TEOS HMDSO hybrid composite \$2organic/\$2organic \$2organic near2 inorganic (interlayer interlevel intermetal) near dielectric ILD BCB)	EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2005/09/17 20:22
S90	8	S89 not (S86 S87 S88)	EPO;	OR	ON	2005/09/17
		505 Not (300 507 300)	JPO; DERWEN T; IBM_TDB			20:23

S91	70	S85 not (S86 S87 S88 S89)	EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2005/09/17 20:24
S92	15	S91 and etch\$3	EPO; JPO; DERWEN T; IBM TDB	OR	ON	2005/09/17 20:24

C02	40	(/::t NO !!N -:	EDO:	OR	ON	2005/00/17
S93	49	((nitrogen N2 "N.sub.2")	EPO;	UK	UN	2005/09/17 20:25
		with (hydrogen H2 "H.	JPO;			20.25
		sub.2" fluorine F2 "F.sub.	DERWEN		•	
		2") (hydrogen H2 "H.sub.	T;			
1		2") with (fluorine F2 "F.	IBM_TDB			
		sub.2") (fluorine F2 "F.				
		sub.2") with (forming adj				
		gas N2/F2 F2/N2)				
		(hydrogen H2 "H.sub.2")				
		with (NF3 "NF.sub.3"				
İ		nitrogentrifluori?e				
		nitrogen adj \$3fluoride)				
		(nitrogen N2 "N.sub.2")				
		with (hydrogen adj				
		fluori?e HF hydrofluoric)				
		(nitrogen N2 "N.sub.2")				
		with (fluorohydrocarbon				
		hydrofluorocarbon CFH				
		CHF fluorocarbon CH2F2				
		CF2H2 CHF3 CF3H CH3F				
		CFH3 "CH.sub.2 F.sub.2"				
		"CF.sub.2 H.sub.2" "CHF.				
		sub.3" "CF.sub.3 H" "CH.				
		sub.3 F" "CFH.sub.3"))				
		same (etch\$3) same				
		(silane siloxane				
		vinyltrimethoxysilane				
		siloxane-containing (Si				
		silicon) adj containing adj				
		(organic polymer) TEOS		,		
		HMDSO hybrid composite				
		\$2organic/\$2organic				
		\$2organic-\$2organic				,
		organic near2 inorganic				
		(interlayer interlevel				
		intermetal) near dielectric				
		ILD BCB)				